



Dr. Kurt Ronse

(imec, Belgium)



Kurt Ronse, Ph.D. has been working in the field of lithography at imec for 35 years with responsibilities ranging from lithography researcher, lithography group manager, advanced patterning department director and advanced lithography program director. Currently is leading the Advanced Patterning Program that is focusing primarily on the insertion of low- NA and high-NA EUV lithography into HVM and on the extendibility of EUVL to the next technology nodes, and to which over 30 companies worldwide participate (chip manufactures, equipment and material suppliers, EDA/software companies).

Prior to joining imec, Ronse received a Ms. and Ph.D. degree in Electrical Engineering from the University of Leuven (Belgium).

Ronse has authored and co-authored numerous publications and is a frequent conference speaker, often times presenting invited and plenary papers, in the field of optical lithography (I-line, deep-UV, 157nm, 193nm, 193nm immersion) and EUVL. He is member of advisory groups of various lithography conferences and has been chairing several lithography conferences. He is member of the editorial board of the SPIE Journal of Micro/Nanolithography, MEMS and MOEMS (JM3).

In 2016, he has been elected Fellow of SPIE for achievements in microlithography and advanced patterning and received the MNE Fellow Award in 2023.